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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/807,116	03/24/2004	Kazutoshi Kaji	62807-175	3682	
	7590 12/22/2004		EXAM	INER	
McDermott, Will & Emery 600, 13th Street, N.W. Washington, DC 20005-3096			WELLS, NIKITA		
			ART UNIT	PAPER NUMBER	•

DATE MAILED: 12/22/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)	Ŭ			
	10/807,116	KAJI ET AL.				
Office Action Summary	Examiner	Art Unit				
	Nikita Wells	2881				
The MAILING DATE of this communication app Period for Reply	pears on the cover sheet with the	orrespondence address				
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.1: after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply - If NO period for reply is specified above, the maximum statutory period of - Failure to reply within the set or extended period for reply will, by statute - Any reply received by the Office later than three months after the mailing - earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be ti y within the statutory minimum of thirty (30) da will apply and will expire SIX (6) MONTHS fron , cause the application to become ABANDONI	nely filed ys will be considered timely. In the mailing date of this communication ED (35 U.S.C. § 133).	on.			
Status ·						
1) Responsive to communication(s) filed on 24 M	l <u>arch 2004</u> .	•				
2a) ☐ This action is FINAL . 2b) ☒ This	action is non-final.					
Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.						
Disposition of Claims	·					
4) ☐ Claim(s) 1-10 is/are pending in the application 4a) Of the above claim(s) is/are withdraw 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-10 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or	wn from consideration.					
Application Papers						
9) The specification is objected to by the Examine 10) The drawing(s) filed on 24 March 2004 is/are: Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the Example 11.	a) accepted or b) objected drawing(s) be held in abeyance. So tion is required if the drawing(s) is of	ee 37 CFR 1.85(a). ojected to. See 37 CFR 1.121	(d).			
Priority under 35 U.S.C. § 119		1				
a) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority application from the International Bureau * See the attached detailed Office action for a list	s have been received. s have been received in Applica rity documents have been receiv u (PCT Rule 17.2(a)).	tion No ed in this National Stage				
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 121504.	4) Interview Summar Paper No(s)/Mail [5) Notice of Informal 6) Other:					

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DETAILED ACTION

Claim Rejections - 35 USC § 112

- 1. The following is a quotation of the first paragraph of 35 U.S.C. 112:
 - The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.
- 2. Claims 1-10 are rejected under 35 U.S.C. 112, first paragraph, as containing subject matter which was not described in the specification in such a way as to enable one skilled in the art to which it pertains, or with which it is most nearly connected, to make and/or use the invention.

The claims are rejected because of poor use of the English language and incorrect usage of the technical words normally accepted in this area of technology. As an example terms that are used throughout the claims and Specification that should be changed are:

"electron beam dispersion portion" should probably be --electron beam energy filter-- or

--electron beam dispersion device--.

"magnetic prism" should probably be --magnetic field sector analyzer-- or --magnetic sector--.

"electron beam incidence means" is vague and should probably be defined as -electron

beam focusing or deflection means with some sort of angle of incidence mentioned--

"electron beam generator" should probably be --electron beam gun or source--.

"element distribution" should probably be --electron beam distribution--.

Claim Rejections - 35 USC § 102

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

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A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

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4. As best as could be understood by the Examiner, assuming corrected usage of the technical words and their meening, claim 1 is rejected under 35 U.S.C. 102(b) as being anticipated by O.L. Krivanek (4,743,756).

With respect to claim 1, O.L. Krivanek discloses (Abstract; Fig. 1; Col. 1, lines 14-23; Col. 3, lines 51-68; Col. 4, lines 5-22) an electron microscope having an energy filter (15) for measuring electron beam energy loss spectra or observing element distribution states by analyzing the energy of an electron beam, wherein the electron beam energy loss spectrum of an electron beam irradiated on a sample surface (12) at a position (Col. 4, lines 18-22) at most 10 micrometers shifted away from the optical axis of said electron microscope has an energy deviation of 1 eV or below relative to that of said electron beam irradiated on said sample surface (12) along the optical axis of said electron microscope.

5. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(e) the invention was described in a patent granted on an application for patent by another filed in the United States before the invention thereof by the applicant for patent, or on an international application by another who has fulfilled the requirements of paragraphs (1), (2), and (4) of section 371(c) of this title before the invention thereof by the applicant for patent.

Claims 2-10 are rejected under 35 U.S.C. 102(e) as being anticipated by Taniguchi et al. (2004/0000641 A1). With respect to these claims, Taniguchi et al. disclose (Abstract; Claim 3; Figs. 1-3; [0005, 0006, 0044-0045]) an electron microscope (1) having an energy filter (22) that

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comprises an energy dispersion means for analyzing the energy of an electron beam (42); and deflection coils (13, 14) respectively disposed on the upstream and downstream sides of said energy dispersion means (22), wherein said deflection coil (13) disposed on the upstream side of said energy dispersion means (22) corrects said electron beam (42) for its path in two directions of perpendicular axes in a plane normal to the optical axis of said energy dispersion means (22), or in two- dimensional way, and said deflection coil (14) disposed on the downstream side of said energy dispersion means (22) corrects said electron beam (42) for its path in a plane normal to said optical axis of said energy dispersion means so that at least one of the directions in which said electron beam (42) is corrected for its path coincides with the energy axis of an energy dispersion plane formed by said energy dispersion means (22). Taniguchi et al. also disclose an electron microscope (1) wherein said electron beam (42) incidence means is composed of one or more deflection coils (13, 14) and the use of a slit (23) for selecting said electron beam on the basis of its energy resulting from the analysis of said electron beam by said energy dispersion means (22).

Specification

6. A substitute specification in proper idiomatic English and in compliance with 37 CFR 1.52(a) and (b) is required. The substitute specification filed must be accompanied by a statement that it contains no new matter.

The disclosure is objected to because of poor use of the English language and incorrect usage of the technical words normally accepted in this area of technology as pointed out in paragraph #2 above.

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Conclusion

- The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Kaji et al. (6,703,613 B2 and 6,794,648 B2) disclose an electron energy loss spectrometer to determine the beam energy loss transmitted through an object to be analyzed. Brink et al. (6,184,524 B1) and Kundmann et al. (5,798,524) disclose an energy filtering system of an energy filtering transmission electron microscope which is automatically adjusted using a computer.
- 8. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Nikita Wells whose telephone number is (571) 272-2484. The examiner can normally be reached on 8:30 AM 5:00 PM. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, John R. Lee can be reached on (571) 272-2477. The central fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306.
- 9. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Nikita Wells, Primary Examiner

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December 16, 2004